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器件制备及器件物理

 $In_xGa_{1-x}N$ 量子阱蓝光LED光电特性与量子阱束缚态能级的关系

李国斌, 陈常水, 刘颂豪

华南师范大学广东省微纳光子功能材料与器件重点实验室激光生命科学教育部重点实验室, 广东 广州 510631

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摘要: 运用软件模拟和理论计算的方法分析了量子阱宽度的变化对量子阱束缚态能级与光电性能产生的影响,建立了束缚态分裂能级理论模型。分析结果表明:当量子阱宽较窄时,极化效应导致的能带弯曲是光谱红移的主要原因,而电子泄漏是导致效率下降的主要原因;当阱宽较大时,能级填充是导致光谱红移的主要原因,俄歇复合与载流子离域是导致效率下降的主要原因。由本文得出,当量子阱宽为2.5~3.5 nm时,InGaN/GaN发光二极管获得最大内量子效率与发光效率。

关键词: 量子阱宽 效率下降 数值模拟 InGaN/GaN发光二极管**Relationship Between $In_xGa_{1-x}N$ Quantum-well Blue LED's Photoelectric Properties and Quantum Well Bound State Energy Level**

LI Guo-bin, CHEN Chang-shui, LIU Song-hao

Laboratory of Nanophotonic Functional Materials and Devices, The Key Laboratory of Laser Life Science, Ministry of Education, South China Normal University, Guangzhou 510631, China

Abstract: The software simulation and theoretical calculations are used to analysis the relationship between $In_xGa_{1-x}N$ quantum well blue LED's photoelectric properties and quantum well bound state energy level. A bound state split level model is established. When the quantum well thickness is narrower, the band bending caused by the polarization effects is the main reason for the spectral red-shift, and electron leakage is the main reason for efficiency droop. But as the well width increase, level filling is the main reason for the red-shift of spectrum, Auger recombination and carrier delocalization are the main reason for lower efficiency. By this article, the optimization quantum well width for InGaN/GaN light-emitting diodes can be obtained. The maximum internal quantum efficiency and luminous efficiency can be obtained when the optimization quantum well width is 2.5~3.5 nm.

Keywords: width of quantum well efficiency droop numerical simulate InGaN/GaN LED

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通讯作者: 陈常水

作者简介: 李国斌(1984-), 男, 湖南衡阳人, 主要从事中红外激光稳频与半导体照明器件的研究。E-mail:

lgb198611@126.com

作者Email: cschen@aiofm.ac.cn

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参考文献:

- [1] Li X, Okur S, Zhang F, et al. Improved quantum efficiency in InGaN light emitting diodes with multi-double-heterostructure active regions[J]. *Appl. Phys. Lett.*, 2012, 101(4):041115-1-4.
- [2] Chen G C, Fan G H. Study on long-wavelength optical phonons in hexagonal InAlGaN crystals[J]. *Chin. J. Lumin.*(发光学报), 2012, 33(8):808-811 (in English).
- [3] Kioupakis E, Patrick R, Delaney K T, et al. Indirect Auger recombination as a cause of efficiency droop in nitride light-emitting diodes[J]. *Appl. Phys. Lett.*, 2011, 98(16):161107-1-3.
- [4] Shen Y C, Mueller G O, Watanabe S, et al. Auger recombination in InGaN measured by photoluminescence [J]. *Appl. Phys. Lett.*, 2007, 91(14):141101-1-3.
- [5] Delaney K T, Patrick R, Kioupakis E, et al. Auger recombination rates in nitrides from first principles[J]. *Appl. Phys. Lett.*, 2009, 94(19):191109-1-3.
- [6] Joachim P, Li S. Electron leakage effects on GaN-based light-emitting diodes[J]. *Opt. Quant. Electron.*, 2011, 42(2):89-95.
- [7] Pope I A, Smowton P M. Carrier leakage in InGaN quantum well light-emitting diodes emitting at 480 nm [J]. *Appl. Phys. Lett.*, 2003, 82(17):2755-2757.
- [8] Mao A, Jaehee C. Reduction of efficiency droop in GaInN/GaN light-emitting diodes with thick AlGaN cladding layers[J]. *Electron. Mater. Lett.*, 2012, 8(1):1-4.
- [9] Meygaard D S, Shan Q F, Dai Q, et al. On the temperature dependence of electron leakage from the active

- [10] Bulashevich K A, Karpov S Y. Is Auger recombination responsible for the efficiency rollover in III-nitride light-emitting diodes? [J]. *Phys. Status Solidi* (c.2008, 5(6):2066-2069 
- [11] Xie J Q, Xian F N, Qian F, et al. On the efficiency droop in InGaN multiple quantum well blue light emitting diodes and its reduction with p-doped quantum well barriers[J]. *Appl. Phys. Lett.*, 2008, 93(12):121107-1-3.
- [12] Kunzer M, Leancu C C, Maier M, et al. Well width dependent luminescence characteristics of UV-violet emitting GaInN QW LED structures[J]. *Phys. Status Solidi* (c.2008, 5(6):2170-2172 
- [13] Reed M L, Readinger E D, Moe C G, et al. Benefits of negative polarization charge in n-InGaN on p-GaN single heterostructure light emitting diode with p-side down[J]. *Phys. Status Solidi* (c.2009, 6(2):585-588 
- [14] Jaehee C, Euijoon Y, Wo J H, et al. Characteristics of blue and ultraviolet light-emitting diodes with current density and temperature[J]. *Electron. Mater. Lett.*, 2010, 6(2):51-53.
- [15] Kim A Y, Steigerwald D A, Wierer J J, et al. Performance of high-power AlInGaN Light emitting diodes[J]. *Phys. Status Solidi* (a.2001, 188(1):15-21 
- [16] Efremov A A, Bochkareva N I, Gorbunov R I, et al. Effect of the joule heating on the quantum efficiency and choice of thermal conditions for high-power blue InGaN/GaN LEDs[J]. *Semiconductors*, 2006, 40(5):605-610.
- [17] Zeng K C, Li J Y, Lin H X, et al. Well-width dependence of the quantum efficiencies of GaN/Al_xGa_{1-x}N multiple quantum wells[J]. *Appl. Phys. Lett.*, 2000, 76(21):3040-3042.
- [18] Smith M, Lin J Y, Jiang H X. Optical transitions in GaN/Al_xGa_{1-x}N multiple quantum wells grown by molecular beam epitaxy[J]. *Appl. Phys. Lett.*, 1996, 69(17):2453-2455.
- [19] Mair R A, Zeng K C, Lin J Y. Optical properties of GaN/AlGaN multiple quantum well microdisks[J]. *Appl. Phys. Lett.*, 1997, 71(20):2898-2900.
- [20] Li Y L, Huang Y R, Lai Y H. Efficiency droop behaviors of InGaN/GaN multiple-quantum-well light-emitting diodes with varying quantum well thickness[J]. *Appl. Phys. Lett.*, 2007, 91(18):181113-1-3.
- [21] Wu J, Walukiewicz W, Yu K M, et al. Small band gap bowing in In_xGa_{1-x}N alloys[J]. *Appl. Phys. Lett.*, 2002, 80(25):4741-4743.
- [22] Levinstein M E, Rumyantsev S L, Shur M S. *Properties of Advanced Semiconductor Materials* [M]. Chichester, UK: Wiley, 2001: 7-8.
- [23] Lu H M, Chen G X. Influence of polarization effect on optoelectronic properties of InGaN/GaN multiple quantum well[J]. *Chin. J. Lumin.* (发光学报), 2011, 32(3):266-271 (in Chinese).